



Patent
Attorney's Docket No. 015290-457

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of) **BOX AF**
Jerome S. HUBACEK et al.)
Application No.: 09/749,916) **Group Art Unit: 1763**
Filed: December 29, 2000) **Examiner: L. Alejandro Mulero**
For: ELECTRODE FOR PLASMA) **Confirmation No.: 6834**
PROCESSES AND METHOD FOR)
MANUFACTURE AND USE THEREOF)

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AMENDMENT AFTER FINAL REJECTION

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

In response to the final Official Action dated September 23, 2002, please amend the
above-identified application as follows:

IN THE CLAIMS:

Please cancel Claims 2, 22, 24 and 26 without prejudice to or disclaimer of the
subject matter therein.

Please replace Claims 1, 3, 10, 23, 27, and 30 as follows:

1. (Amended) A low resistivity silicon electrode adapted to be mounted in a
plasma reaction chamber used in semiconductor substrate processing, comprising:
a silicon electrode comprising a showerhead electrode having a plurality of gas
outlets arranged to distribute process gas in the plasma reaction chamber during use of the
showerhead electrode, the electrode having a thickness of about 0.3 inch to 0.5 inch and an
electrical resistivity of less than 1 ohm-cm, the electrode having an RF driven or

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